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## PATENT ABSTRACTS OF JAPAN

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(71)Applicant : JAPAN SYNTHETIC RUBBER CO LTD

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**(54) RADIATION SENSITIVE COMPOSITION****(57)Abstract:**

PROBLEM TO BE SOLVED: To obtain a compsn. effectively sensitive to various radiations, having satisfactory resolution, pattern shape and PED stability and low dependency on baking temp., excellent also in process stability and useful as a chemically amplified positive resist by incorporating a polymer having substituents each having a t-butyl group cleavable by an acid, a polymer having acetal or ketal groups and a radiation sensitive acid generating agent.

SOLUTION: This compsn. contains a polymer having substituents each having a t-butyl group cleavable by an acid, a compd. having acetal or ketal groups decomposable by the acid and a radiation sensitive acid generating agent. This compsn. is excellent in PED stability as well as excellent especially in resolution and pattern shape, has low dependency on baking temp., is excellent in process stability and can stably form a high precision fine pattern.

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